IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

CENTRAL PAX CENTER

Applicant(s): Chih-Ming Ke

(CONF 4511) Application No.: 10/047,266

Group Art Unit: 1765

Kin Chan Chen

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Examiner:

Title: Reducing photoresist shrinkage via plasma

treatment

Commissioner for Patents Alexandria, VA 22313-1450

Attorney Docket No.: 67,200-641

Do not enter.

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REQUEST FOR RECONSIDERATION

Dear Sir:

In response to a final Office Action dated Dec. 11, 2003, please enter the following amendment and consider the following remarks.